



A35-13-PCT-USA (072944.0155)  
PATENT

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PCT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Kim et al.

U.S. Application No.: 10/070,477

Examiner: Not Yet Assigned

International Appln. No.: PCT/KR00/00956

Group Art Unit: Not Yet Assigned

International Filing Date: August 25, 2000

For: POLYMER FOR CHEMICALLY AMPLIFIED RESIST  
AND A RESIST COMPOSITION USING THE SAME

INFORMATION DISCLOSURE STATEMENT

I hereby certify that this paper is being deposited with the United States Postal Service as First Class Mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, D.C. 20231, on:

July 19, 2002  
Date of Deposit

Tara E. Agnew  
Agent Name

50,589  
PTO Registration No.

Tara E. Agnew  
Signature

July 19, 2002  
Date of Signature

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DEC 27 2002  
TC 1700

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

Pursuant to 37 C.F.R. §§ 1.56, 1.97 and 1.98, Applicants, by their attorneys, respectfully request that the documents, which are listed below and in the attached PTO Form 1449, be "made of record" in the above-identified patent application. Copies of these documents are enclosed herewith.

1. U.S. Patent No. 5,773,191 to Padmanaban et al.
2. U. S. Patent No. 5,679,495 to Yamachika et al.
3. U.S. Patent No. 5,556,734 to Yamachika et al.
4. U.S. Patent No. 5,492,793 to Breyta et al.
5. U.S. Patent No. 5,443,690 to Takechi et al.
6. U.S. Patent No. 5,310,619 to Crivello et al.
7. U.S. Patent No. 4,491,628 to Ito et al.
8. European Patent Application No. 0 877 294 A1.
9. European Patent Application No. 0 793 144 A2.
10. European Patent Application No. 0 786 701 A1.
11. European Patent Application No. 0 404 206 A2.
12. Japanese Patent No. 05-249683.
13. Japanese Patent No. 05-232706.
14. Japanese Patent No. 05-113667.
15. Japanese Patent No. 2-27660.
16. MacDonald et al., "Airborne Chemical Contamination of a Chemically Amplified Resist," *SPIE*, Vol. 1466 (1991).
17. Schlegel, 37th Japanese Applied Physics Society Announcement, 28p-ZE-4 (1990).
18. Ueno et al., 36th Japanese Applied Physics Society Announcement, 1p-k-7, (1989).
19. Ito et al., "Applications of Photoinitiators to the Design of Resists for Semiconductor Manufacturing," *Polymers in Electronics*, American Chemical Society, pp. 11-23 (1984).

Several of the above-identified documents were cited in the International Search Report mailed on March 9, 2001 for PCT Application Serial No.

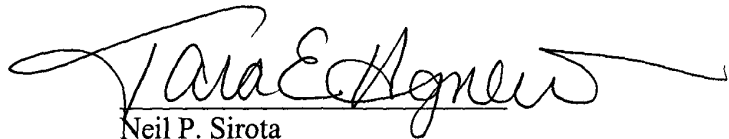
PCT/KR00/00956, and a copy of the Search Report has already been provided to the

Patent Office. English-language abstracts for the Japanese patents referenced as numbers 12-14 in the list above have been provided herewith. Additionally, EP 0 404 206 A2, a copy of which is enclosed herewith, corresponds to Japanese Patent No. 2-27660. Lastly, copies of the references listed as numbers 17 and 18 in the above list were not readily available to Applicants. However, copies of these documents will be provided when they become available to Applicants.

The Commissioner is hereby authorized to charge payment of any fees or credit any overpayment necessitated by this communication to Deposit Account No. 02-4377.

Respectfully submitted,

Dated: July 19, 2002



Neil P. Sirota  
Patent Office Reg. No. 38,306

Attorney for Applicants  
(212) 408-2548

Tara E. Agnew  
Patent Office Reg. No. 50,589

Agent for Applicants  
(212) 408-2654

BAKER BOTTS L.L.P.  
30 Rockefeller Plaza  
New York, New York 10112-0228

Enclosures

<b>Form PTO-1449 U.S. Department of Commerce (REV. 2-82) Patent and Trademark Office</b>  <b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (Use several sheets if necessary)	Atty. Docket No. A35043-PCT-USA (072944.0155)	U.S. Application No. 10/070,477 International Appln. No. PCT/KR00/00956
	Applicants Kim et al.	
	International Filing Date August 25, 2000	Group To be assigned
	<div style="border: 1px solid black; padding: 5px; transform: rotate(-15deg); display: inline-block;"> <b>RECEIVED</b>            DEC 27 2002            TC 1700         </div>	

### U.S. PATENT DOCUMENTS

*Exam. Init.			Document No.							Date	Name	Class	Subclass	Filing Date if Appro.
			5	7	7	3	1	9	1	6/30/1998	Padmanaban et al.			
			5	6	7	9	4	9	5	10/21/1997	Yamachika et al.			
			5	5	5	6	7	3	4	9/17/1996	Yamachika et al.			
			5	4	9	2	7	9	3	2/20/1996	Breyta at al.			
			5	4	4	3	6	9	0	8/22/1995	Takechi et al.			
			5	3	1	0	6	1	9	5/10/1994	Crivello et al.			
			4	4	9	1	6	2	8	1/1/1985	Ito et al.			

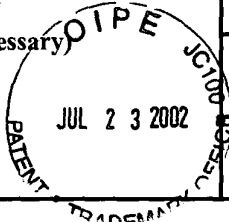
### FOREIGN PATENT DOCUMENTS

	Document No.									Date	Country	Class	Subclass	Translation	
														Yes	No
	0	8	7	7	2	9	4	A	1	11/11/1998	EP				
	0	7	9	3	1	4	4	A	2	9/03/1997	EP				
	0	7	8	6	7	0	1	A	1	7/30/1997	EP				
	0	4	0	4	2	0	6	A	2	5/2/1983	EP				

NY02:392102.1 Examiner

Date Considered

\* Examiner: Initial citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<b>Form PTO-1449 U.S. Department of Commerce (REV. 2-82) Patent and Trademark Office</b>  <b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (Use several sheets if necessary)	Atty. Docket No. A35043-PCT-USA (072944.0155)	U.S. Application No. 10/070,477 International Appln. No. PCT/KR00/00956
	Applicants Kim et al.	
	International Filing Date August 25, 2000	Group To be assigned
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Document No.										Date	Country	Class	Subclass	Translation	
														Yes	No
		0	5	2	4	9	6	8	3	9/28/1993	JP				
		0	5	2	3	2	7	0	6	9/10/1993	JP				
		0	5	1	1	3	6	6	7	5/7/1993	JP				
				2	2	7	6	6	0	1990	JP				

**OTHER DOCUMENTS (including Author, Title, Date, Pertinent Pages, Etc.)**

		MacDonald et al., "Airborne Chemical Contamination of a Chemically Amplified Resist," <i>SPIE</i> , Vol. 1466 (1991).
		Schlegel, 37th Japanese Applied Physics Society Announcement, 28p-ZE-4 (1990).
		Ueno et al., 36th Japanese Applied Physics Society Announcement, 1p-k-7, (1989).
		Ito et al., "Applications of Photoinitiators to the Design of Resists for Semiconductor Manufacturing," <i>Polymers in Electronics</i> , American Chemical Society, pp. 11-23 (1984).

NY02:392102.1 Examiner

Date Considered

\* Examiner: Initial citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.